

L Number	Hits	Search Text	DB	Time stamp
1	4711	in-situ and semiconductor	USPAT; EPO; JPO; DERWENT	2002/01/26 17:26
2	2895	(in-situ and semiconductor) and (thermal or anneal\$4)	USPAT; EPO; JPO; DERWENT	2002/01/26 17:27
3	1486	((in-situ and semiconductor) and (thermal or anneal\$4)) and anneal\$4	USPAT; EPO; JPO; DERWENT	2002/01/26 17:29